

8 7 6 5 4 3 2 1

**NOTES CONTINUED:**  
 ⑤ SCRIBE, ENGRAVE, OR MECHANICALLY STAMP (NO INKS OR DYES) DRAWING PART NUMBER, REVISION (AND VARIANT OR "TYPE" IF APPLICABLE) ON NOTED SURFACE OF PART FOLLOWED ON THE NEXT LINE WITH A THREE DIGIT SERIAL NUMBER. SERIAL NUMBERS START AT 001 FOR THE FIRST ARTICLE AND PROCEED CONSECUTIVELY, USE MINIMUM 0.12" HIGH CHARACTERS, UNLESS THE SIZE OF THE PART DictATES SMALLER CHARACTERS.  
 A VIBRATORY TOOL MAY BE USED.  
 EXAMPLE: DXXXXXX-YY, TYPE-XX, S/N XXX

6. APPROXIMATE WEIGHT = 35.96 LB [16.31 KG].

7. MACHINE ALL SURFACES TO REMOVE OXIDES AND MILL FINISH, USE OF ABRASIVE REMOVAL TECHNIQUES IS NOT ALLOWED.

8. ALL PARTS SHALL BE MANUFACTURED IN ACCORDANCE WITH LIGO SPECIFICATION E0900364.

9. ALL MATERIAL IS TO BE VIRGIN MATERIAL (i.e. NOT WELD REPAIRS OR PLUGS UNLESS APPROVED IN ADVANCE IN WRITING BY LIGO, REFER TO LIGO-E0900364).

10. NO REPAIRS SHALL BE MADE UNLESS APPROVED IN ADVANCE, AND IN WRITING, BY LIGO LABORATORY. IN GENERAL WELD REPAIRS AND PRESS FIT INSERT REPAIRS ARE NEVER ACCEPTABLE; THE MATERIAL SHOULD BE MADE WITH VIRGIN MATERIAL. SPECIAL CIRCUMSTANCES CAN BE REVIEWED IF / WHEN BROUGHT TO THE ATTENTION OF LIGO CONTRACTING OFFICER'S REPRESENTATIVE (COTR) THROUGH A MATERIAL REVIEW BOARD (MRB) PROCESS, REFER TO LIGO-E0900364.

(11) ALL TAPPED HOLES: .005 OVERSIZE BOTH DRILL AND TAP. (SHT. 2)

D

D

C

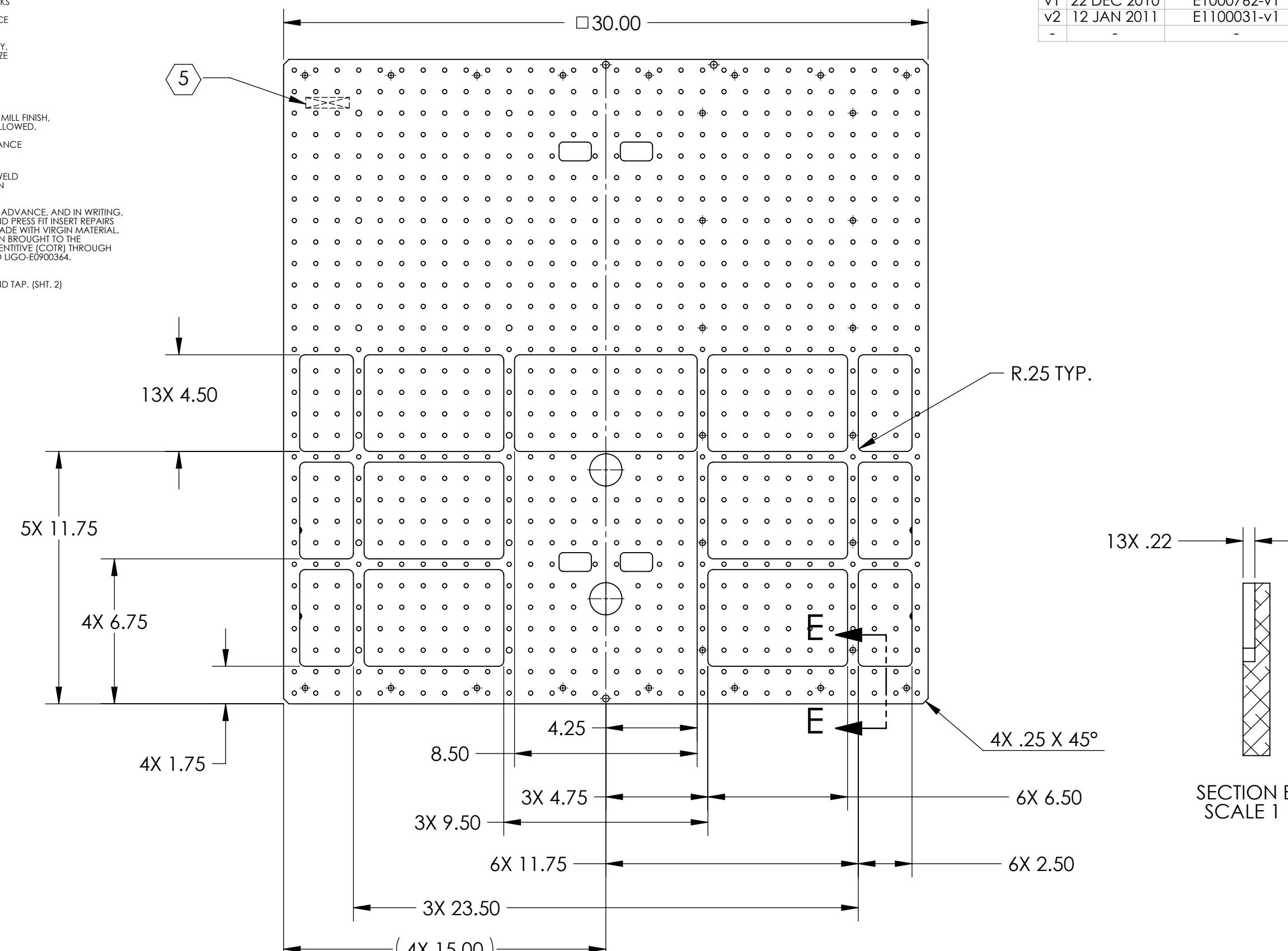
C

B

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A

A



D1001129 aLIGO ETM OPTICAL TABLE, PART PDM REV: X-065, DRAWING PDM REV: X-078

NOTES AND TOLERANCES: (UNLESS OTHERWISE SPECIFIED)	
DIMENSIONS ARE IN INCHES	1. INTERPRET DRAWING PER ASME Y14.5-1994.
TOLERANCES: XX $\pm .01$ XXX $\pm .005$	2. REMOVE ALL SHARP EDGES, R.02 MIN.
ANGULAR $\pm 1.0^\circ$	3. DO NOT SCALE FROM DRAWING.
	4. ALL MACHINING FLUIDS MUST BE FULLY SYNTHETIC, FULLY WATER SOLUBLE AND FREE OF SULFUR, SILICONE, AND CHLORINE.
MATERIAL	6061-T6 Al
FINISH	63 $\mu$ inch Ra

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LIGO CALIFORNIA INSTITUTE OF TECHNOLOGY  
 MASSACHUSETTS INSTITUTE OF TECHNOLOGY  
 SYSTEM ADVANCED LIGO SUB-SYSTEM AOS  
 NEXT ASSY D1001160

DESIGNER	K. MAILAND	10/09/2010	SIZE	DWG. NO.	REV.
DRAFTER	M. MILLER	11/09/2010	B	D1001129	v2
CHECKER					
APPROVAL					

SCALE: 1:5 PROJECTION: SHEET 1 OF 3

